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U.S. UTILITY Patent Application

PATENT NUMBER and
ISSUE DATE

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10084204	02/28/2002	430		1752	

****APPLICANTS:** Suzuki Takako; Tamura Sachiko; Doi Kousuke; Kohara Hidekatsu;
Nakayama Toshimasa;

****CONTINUING DATA VERIFIED:**
THIS APPLICATION IS A DIV OF 09/322,978 06/01/1999

**** FOREIGN APPLICATIONS VERIFIED:**
JAPAN 10-155213 06/04/1998

PG-PUB ☐ DO NOT PUBLISH ☐

RESCIND ☐

Foreign priority claimed ☐ yes ☐ no
35 USC 119 conditions met ☐ yes ☐ no
Verified and Acknowledged Examiners's initials

ATTORNEY DOCKET NO

Q67844

TITLE : Positive photoresist composition and process for forming resist pattern using same

U.S. DEPT. OF COMM./PAT. & TM.-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
			Total Claims	Print Claim for O.G.
ISSUE FEE		Primary Examiner	DRAWING	
Amount Due	Date Paid		Sheets Drwg.	Figs. Drwg.
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE	Application Examiner	
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